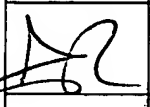


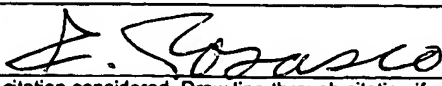


Substitute Form PTO-1449 (Modified)	U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. 10559-892001	Application No. New application
Information Disclosure Statement by Applicant (Use several sheets if necessary) (37 CFR §1.98(b))		Applicant Peng Liu et al.	
		Filing Date February 27, 2004	Group Art Unit Unknown
IDS filed 02/27/2004			


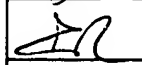


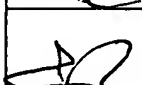

U.S. Patent Documents							
Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						

Foreign Patent Documents or Published Foreign Patent Applications								
Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Translation	
							Yes	No
	AL							
	AM							
	AN							
	AO							
	AP							


Other Documents (include Author, Title, Date, and Place of Publication)		
Examiner Initial	Desig. ID	Document
	AQ	"Domain decomposition methods for simulation of printing and inspection of phase defects"; Michael Lam et al.; Department of Electrical Engineering and Computer Sciences, University of CA-Berkeley, Berkeley, CA 94720; m1Lam@eecs.berkeley.edu
	AR	"Boundary Layer Model to Account for Thick Mask Effects in PhotoLithography"; Jaione Tirapu-Azpiroz et al.; Electrical Engineering Dept., UCLA, Los Angeles, CA 90095-1594; jaione@ee.ucla.edu
	AS	"Simplified Models for Edge Transitions in Rigorous Mask Modeling"; Konstantinos Adam et al.; EECS Dept., University of CA at Berkeley, Berkeley, CA 94720; kadam@eecs.berkeley.edu

Examiner Signature 	Date Considered 9/06
EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	

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Other Documents (include Author, Title, Date, and Place of Publication)		
Examiner Initial	Desig. ID	Document
	AT	Fast rigorous three-dimensional mask diffraction simulation using Battle-Lemarie wavelet-based multiresolution time-domain method, M. S. Yeung, Boston Univ. [5040-07] SPIE 2003, Vol 5040, p69
	AU	Fast topography simulation using differential method, S. Y. Zinn, S. Kim, S. Choi, J. Sohn, Samsung Electronics Co., Ltd. (South Korea) [5040-09] SPIE 2003, Vol 5040, p92
	AV	Rigorous 3D simulation of phase defects in alternating phase-shifting masks. Pistor, T.V.; Proceedings of the SPIE - The International Society for Optical Engineering, vol.4562, 2002. p. 1038-50. Conference Paper.
	AW	Enhancements in rigorous simulation of light diffraction from phase-shift masks. Erdmann, A.; Kachwala, N.; Proceedings of the SPIE - The International Society for Optical Engineering, vol.4691, 2002. p. 1156-67. Conference Paper.
	AX	METROPOLE-3D: an efficient and rigorous 3D photolithography simulator. Strojwas, A.J.; Li, X.; Lucas, K.D.; IEICE Transactions on Electronics, vol.E82-C, no.6, June 1999. p. 821-9. Journal Paper.
	AY	Lithography simulation employing rigorous solutions to Maxwell's equations. Gordon, R.; Mack, C.A.; Proceedings of the SPIE - The International Society for Optical Engineering, vol.3334, 1998. p. 176-96. Conference Paper.

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